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Docket No.: SON-2628
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Shinji Omori

Application No.: 10/509,230

Confirmation No.: 1800

Filed: September 24, 2004

Art Unit: 2881

For: MASK PATTERN CORRECTION METHOD,
PRODUCTION METHOD OF
SEMICONDUCTOR DEVICE, MASK
PRODUCTION METHOD AND MASK

Examiner: Nikita Wells

AMENDMENT UNDER 37 C.F.R. 1.312
AFTER ALLOWANCE AND BEFORE PAYMENT OF THE ISSUE FEE

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Subsequent to the Notice of Allowance mailed July 27, 2005, but before payment of the issue fee, please amend the above-identified application as follows: